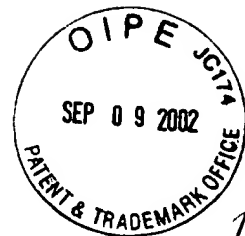


1711



Docket No. 209236US0

IN RE APPLICATION OF: Toshihiro OGAWA, et al.

SERIAL NO: 09/867,541

FILED: May 31, 2001

FOR: COMPOSITION FOR POLISHING PAD AND POLISHING PAD USING THE SAME

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

SIR:

Transmitted herewith is an amendment with marked-up copy in the above-identified application.

- ☐ No additional fee is required
- ☐ Small entity status of this application under 37 C.F.R. §1.9 and §1.27 is claimed.
- ☒ Additional documents filed herewith: Copy: In re Clay

The Fee has been calculated as shown below:

CLAIMS	CLAIMS REMAINING		HIGHEST NUMBER PREVIOUSLY PAID	NO. EXTRA CLAIMS	RATE	CALCULATIONS
TOTAL	14	MINUS	20	0	x \$18 =	\$0.00
INDEPENDENT	4	MINUS	3	1	x \$84 =	\$84.00
		<input type="checkbox"/> MULTIPLE DEPENDENT CLAIMS			+ \$280 =	\$0.00
		TOTAL OF ABOVE CALCULATIONS				\$84.00
		<input type="checkbox"/> Reduction by 50% for filing by Small Entity				\$0.00
		<input type="checkbox"/> Recordation of Assignment			+ \$40 =	\$0.00
		TOTAL				\$84.00

- ☒ A check in the amount of **\$84.00** is attached.
- ☒ Please charge any additional Fees for the papers being filed herewith and for which no check is enclosed herewith, or credit any overpayment to deposit Account No. 15-0030. A duplicate copy of this sheet is enclosed.
- ☒ If these papers are not considered timely filed by the Patent and Trademark Office, then a petition is hereby made under 37 C.F.R. §1.136, and any additional fees required under 37 C.F.R. §1.136 for any necessary extension of time may be charged to Deposit Account No. 15-0030. A duplicate copy of this sheet is enclosed.



22850

Customer Number 22850
Tel. (703) 413-3000
Fax. (703) 413-2220
(OSMMN 10/01)

OBLON, SPIVAK, McCLELLAND,
MAIER & NEUSTADT, P.C.

Norman F. Oblon

Registration No. 24,618

Harris A. Pitlick

Registration No. 38,779

RECEIVED
SEP 13 2002
TC 1700

209236US-0



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF:

TOSHIHIRO OGAWA ET AL

SERIAL NO.: 09/867,541

FILED: MAY 31, 2001

FOR: COMPOSITION FOR POLISHING PAD :
AND POLISHING PAD USING THE SAME

:

: GROUP ART UNIT: 1711

:

: EXAMINER: RAJGURU, U.

#5/a
9/16/02
7c

AMENDMENT

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

RECEIVED
SEP 13 2002
TC 1700
#5

SIR:

Responsive to the Office Action dated June 7, 2002, Applicants respectfully request reconsideration of the above-identified application in view of the following amendment and remarks.

#4

IN THE CLAIMS

Please amend Claim 1 as follows:

a 1. (Amended) A composition for a polishing pad which comprises a water-insoluble matrix material containing a crosslinked polymer and a water-soluble particle dispersed in the water-insoluble matrix material, wherein the elongation remaining after breaking is 100% or less when a test piece comprising said water-insoluble matrix material is broken at 80°C.

Please cancel Claim 2.

Please amend Claim 3 as follows:

a 2 3. (Amended) The composition for a polishing pad according to claim 1, wherein said water-insoluble matrix material is modified with at least one selected from the group

09/10/2002 TBESHAH1 00000030 09867541

01 FC:102

84.00 OP